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Information Disc		Applicant Chris E. Barns et al.			
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U.S. Patent Documents							
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Foreign Patent Documents or Published Foreign Patent Applications								
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·	Other D	ocuments (include Author, Title, Date, and Place of Publication)
Examiner Designitial ID		Document
L.V	AC	Ducroquet et al., "Full CMP Integration," IEEE Transactions on Electron Devices, 48(8):1816-1821, 2001
	AD	Matsuda et al., "Performance Improvement of Metal," Symposium on VLSI Technology Digest of Technical Papers, 2001
	AE	Ushiki et al., "Reliable Tantalum-Gate," IEEE Transactions on Electron Devices, 44(9):1467-1472, 1997
	AF	Yagishita et al., "Improvement of Threshold Voltage," IEEE Transactions on Electron Devices, 48(8):1604-1611, 2001
	AG	Planar Solutions Announces New Second Step Copper CMP Slurry," Arch SemiConductor Photopolymers: About Us
	AH	Conaghan et al., "Applications of silicides in semiconductor processing,"
	AI	Abstract, Cabot Microelectronics Corporation, Semiconductor Products, 2000
	· AJ	Abstract, Cabot Microelectronics Corporation, FAX (Frequently Asked Questions), 2000

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